Claims

1. A method for exposure of a photosensitive coating (3), comprising at least a first photosensitive area (3a) and a second photosensitive area (3b), wherein the first area (3a) reacts to photons of a first wavelength and the second area (3b) reacts to photons of a second wavelength, wherein the first wavelength is different from the second wavelength, wherein the method comprises the following steps, in particular in the following sequence:

   - exposure of the coating (3) to the photons of the first wavelength,

   - exposure of the coating (3) to the photons of the second wavelength,

   wherein there is no focus of the photons on the photosensitive areas (3a,3b).

2. The method according to claim 1, wherein the coating (3) is exposed by means of a dynamically controllable unit, in particular by means of a digital micromirror unit (7).

3. The method according to at least one of the preceding claims, wherein the coating (3) is exposed by means of at least one mask (15a, 15b).

4. The method according to at least one of the preceding claims, wherein the exposure of the coating (3) to the photons of the first wavelength produces a photochemical reaction only in the first area (3a) and the exposure of the coating (3) to the photons of the second wavelength produces a photochemical reaction only in the second area (3b).

5. The method according to at least one of the preceding claims, wherein the coating (3) is exposed in a spatially resolved and/or punctual manner, particularly by means of beam bundles.

6. The method according to at least one of the preceding claims, wherein the coating (3) is exposed by an individually controllable photon source (5), wherein the wavelength and/or the dose of the photons is/are adjusted.

7. The method according to at least one of the preceding claims, wherein the coating (3) is exposed by positioning a filter (6a, 6b) in front of a broad-band photon source (5), wherein the wavelength and/or the dose is/are adjusted.

8. The method according to at least one of the preceding claims, wherein different depth regions of the coating (3) react after one another.

9. The method according to at least one of the preceding claims, wherein the coating (3) has sensitivities for photons of the same wavelength which vary over a thickness of the coating (3).

10. The method according to at least one of the preceding claims, wherein the first area (3a) is constituted as a first layer and the second area (3b) is constituted as a second layer on the first layer.

11. A device for the exposure of a photosensitive coating (3), comprising at least a first photosensitive area (3a) and a second photosensitive area (3b), wherein the first photosensitive area (3a) reacts to photons of a first wavelength and the second photosensitive area (3b) reacts to photons of a second wavelength, wherein the first wavelength is different from the second wavelength, comprising a radiation device (5) for the exposure of the coating (3) to the photons of the first wavelength and for the exposure of the coating (3) to the photons of the second wavelength,

    wherein there is no focus of the photons on the photosensitive areas (3a,3b).

12. The device according to claim 11, comprising a dynamically controllable unit, in particular a digital micromirror unit (7), for the exposure of the coating (3).

13. The device according to at least one of the preceding claims, comprising at least one mask (15a, 15b) for the exposure of the coating (3).

14. The device according to at least one of the preceding claims, comprising a mobile support for moving the coating (3) with respect to the radiation device (5).